PENDING CLAIMS:

- 1. (Original) An electronic element comprising a deposited film containing cesium, said deposited film comprising a plurality of projections composed of cesium oxide on a surface thereof.
- 2. (Original) An electronic element according to claim 1, wherein said deposited film comprises an amorphous film of carbon, and said projections are conical and have an average height h in a range of 10 nm < h < 500 nm.
- 3. (Original) An electronic element according to claim 2, wherein said amorphous film of carbon is formed by an ion beam deposition process using a negative ion beam.
- 4. (Original) An electronic element according to claim 2, wherein said amorphous film of carbon is a cold cathode element which emits electrons when an electric filed is applied to said cold cathode element.
- 5. (Original) An electronic element according to claim 3, wherein said amorphous film of carbon is a cold cathode element which emits electrons when an electric field is applied to said cold cathode element.

- 6. (Original) An electronic element, comprising a main body that is formed of an amorphous film of carbon and that contains a metal element having a metal bond radius equal to or larger than two times the atom radius of carbon, and a surface layer that covers said main body and is formed of an amorphous film of carbon having a high sp³ hybridization.
- 7. (Original) An electronic element according to claim 6, wherein said surface layer, a half-value width Hw of a photoelectron spectrum of C₁₅ electrons by an X-ray photoelectron spectroscopic analysis is equal to or smaller than 2.0 eV.
- 8. (Original) An electronic element according to claim 6, wherein said main body has, on an interface thereof to said surface layer, a plurality of projections containing said metal element, and said surface layer has a plurality of protrusions formed to conform to said projections.
- 9. (Original) An electronic element according to claim 7, wherein said main body has, on an interface thereof to said surface layer, a plurality of projections containing said metal element, and said surface layer has a plurality of protrusions formed to conform to said projections.
- 10. (Original) An electronic element according to claim 8, wherein said metal element is cesium or rubidium.

- 11. (Original) An electronic element according to claim 9, wherein said metal element is cesium or rubidium.
- 12. (Original) An electronic element according to claim 10, wherein each of said main body and said surface layer is formed by an ion beam deposition process.
- 13. (Original) An electronic element according to claim 11, wherein each of said main body and said surface layer is formed by an ion beam deposition process.
- 14. (Original) An electronic element according to claim 12, wherein said electronic element is used as a cold cathode element that emits electrons with application of an electric field to said cold cathode element.
- 15. (Original) An electronic element according to claim 13, wherein said electronic element is used as a cold cathode element that emits electrons with application of an electric field to said cold cathode element.
- 16. (Original) An electronic element comprising a main body composed of an amorphous film of carbon, and a surface layer that covers said main body and that is formed of an amorphous film of carbon having a high sp³ hybridization.

- 17. (Original) An electronic element according to claim 16, wherein said electronic element is used as a cold cathode element that emits electrons with application of an electric field to said cold cathode element.
- 18. (Original) An electronic element according to claim 10, wherein said metal element is cesium contained in a range of form 0.1 % by atom to 5.0 % by atom in the amorphous film of carbon.
- 19. (Original) An electronic element according to claim 11, wherein said metal element is cesium contained in a range of form 0.1% by atom to 5.0% by atom in the amorphous film of carbon.